

Notice of References Cited

Application/Control No.

10/696,276

Applicant(s)/Patent Under
Reexamination
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Examiner

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Art Unit

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Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Cobb, N., and A. Zakhor, "Fast, Low-Complexity Mask Design," Proceedings of SPIE, vol. 2440: Symposium on Optical/Laser Microlithography VIII, Santa Clara, Calif., Feb. 22-24, 1995, pp. 313-327
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